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Substitute for form 1449A/PTO  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (use as many sheets as necessary)				<b>Complete If Known</b>	
Application Number		101/10480			
Filing Date		26 September 2003 (herewith)			
First Named Inventor		Christophe Pierrat et al.			
Group Art Unit					
Examiner Name					
Attorney Docket Number		FTIS 1002-1			
Sheet	1	of	2		

U.S. PATENT DOCUMENTS						
Examiner Initials*	Cite No. <sup>1</sup>	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code <sup>2</sup> (if known)			
EP	A1	5,121,256		Corle et al.	06-09-1992	359 664
EP	A2	5,469,299		Nagano	11-21-1995	359 661
EP	A3	5,982,558		Further et al.	11-09-1999	359 649
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	A11					
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	A15					
	A16					
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	A19					
	A20					

FOREIGN PATENT DOCUMENTS								
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document			Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T
		Office <sup>3</sup>	Number <sup>4</sup>	Kind Code <sup>5</sup> (if known)				
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Examiner Signature		Date Considered	12/6/04
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Substitute for form 1449B/PTO  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  <i>(use as many sheets as necessary)</i>				<b>Complete If Known</b>		
Sheet		2	of	2	Application Number Filing Date First Named Inventor Group Art Unit Examiner Name Attorney Docket Number	26 September 2003 (herewith) Christophe Pierrat et al.    FTIS 1002-1

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
91	C1	FRENCH, ROGER H., et al., "Fluoropolymers for 157nm Lithography: Optical Properties from VUV Absorbance and Ellipsometry Measurements," SPIE Proceedings, Microlithography 2000, 12 pages.	
91	C2	FLAGELLO, DONIS G., et al., "High-numerical-aperture effects in photoresist," Applied Optics 36(34) (1 Dec 1997) 8944-8951.	
91	C3	FRENCH, ROGER H., et al., "Materials Design and Development of Fluoropolymers for Use as Pellicles in 157nm Photolithography," Optical Microlithography XIV, Proceedings of SPIE vol. 4346 (2001).	
91	C4	PIERRAT, CHRISTOPHE, et al., "The MEF Revisited: Low k1 Effects versus Mask Topography Effects," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (25 Feb 2003).	
91	C5	CHIBA, YUJI, et al., "New generation projection optics for ArF lithography," Optical Microlithography XV, Proceedings of SPIE Vol. 4691 (2002), 679-686.	
91	C6	BAEK, SO-YEON, et al., "Simulation Study of Process Latitude for Liquid Immersion Lithography," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (27 Feb 2003), 11 pages.	
91	C7	PENDRY, J.B., et al., "Near-field lenses in two dimensions," J. Phys.: Condens. Matter 14 (2002) 8463-8479.	
91	C8	OBER, CHRISTOPHER K., "Polymer Surfaces and Surface Analysis," Nanobiotechnology MSE 563/AEP 663 (2000), 43 pages.	
91	C9	HAFEMAN, SCOTT, et al., "Simulation of imaging and stray light effects in immersion lithography," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (27 Feb 2003), 13 pages.	
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Examiner Signature <span style="float: right; font-family: cursive;">[Signature]</span>	Date Considered	12/6/04
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